# F TENT COOPERATION TREA Y

To:

#### From the INTERNATIONAL BUREAU

### **PCT**

#### **NOTIFICATION OF ELECTION**

(PCT Rule 61.2)

Commissioner
US Department of Commerce
United States Patent and Trademark
Office, PCT
2011 South Clark Place Room
CP2/5C24
Arlington, VA 22202

Date of mailing (day/month/year)
15 February 2001 (15.02.01)

International application No.
PCT/SE00/01134

International filing date (day/month/year)
31 May 2000 (31.05.00)

Applicant

BRIAND, Danick et al

	The decimated Office in hearby position of its election made:
1.	The designated Office is hereby notified of its election made:
	X in the demand filed with the International Preliminary Examining Authority on:
	20 December 2000 (20.12.00)
	in a notice effecting later election filed with the International Bureau on:
2.	The election X was
	was not
	made before the expiration of 19 months from the priority date or, where Rule 32 applies, within the time limit under Rule 32.2(b).

The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland Authorized officer

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## $\lambda TENT$ COOPERATION TRE. /Y

	From the INTERNATIONAL BURE	AU
PCT	То:	
NOTIFICATION OF THE RECORDING OF A CHANGE  (PCT Rule 92bis.1 and Administrative Instructions, Section 422)  Date of mailing (day/month/year)	BERGLUND, Erik Berglunds Patentbyrå AB Aspebråten S-590 55 Sturefors SUÈDE	
04 October 2001 (04.10.01)		
Applicant's or agent's file reference P9918PC	IMPORTANT NOTIFICA	ATION
International application No. PCT/SE00/01134	International filing date (day/month/year) 31 May 2000 (31.05.00)	
The following indications appeared on record concerning:      the applicant the inventor	the agent the common rep	presentative
Name and Address  NORDIC SENSOR TECHNOLOGIES AB Teknikringen 6	State of Nationality State SE Telephone No.	ate of Residence SE
S-583 30 Linköping Sweden	Facsimile No.	
	Teleprinter No.	
2. The International Bureau hereby notifies the applicant that the the person X the name the add		erning: the residence
Name and Address  APPLIEDSENSOR SWEDEN AB	State of Nationality Sta	ate of Residence SE
Teknikringen 6 S-583 30 Linköping Sweden	Telephone No.	
	Facsimile No.	
	Teleprinter No.	
3. Further observations, if necessary:		
4. A copy of this notification has been sent to:		
X the receiving Office	the designated Offices conce	
the International Searching Authority  X the International Preliminary Examining Authority	the elected Offices concerne other:	ed :
	Authorized officer	
The International Bureau of WIPO 34, chemin des Colombettes 1211 Geneva 20, Switzerland	Athina NICKITAS	-ETIENNE
Facsimile No : (41-22) 740 14 35	elenhone No.: (41-22) 338.83.38	

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#### PCT/SE00/01134

### 7 **Claims**

- 1. Micro-hotplate device with integrated chemical sensor, which comprises:
  - a) a support substrate;
  - a supported membrane, attached to said support substrate, extending over a well in said support substrate;
  - an island attached to said membrane so as to be electrically and thermally isolated from said substrate, said island consisting at least partly of a semiconducting material;
  - d) one or several heating elements integrated in said island;
- e) one or several temperature-sensing elements integrated in said island;
  - f) one or several active microelectronic devices integrated in said island, where at least one of said active microelectronic devices is a chemical sensor whose chemically active layer is exposed to the ambient.
- 2. A micro-hotplate device according to claim 1, wherein at least one heating element consists of a heating transistor.
  - 3. A micro-hotplate device according to claim 1, wherein at least one heating element consists of a heating resistor.
  - 4. A micro-hotplate device according to any of the claims 1-3, wherein at least one temperature-sensing element is a temperature-sensitive resistor.
  - 5. A micro-hotplate device according to any of the claims 1-3, wherein at least one temperature-sensing element is a temperature-sensitive diode.
  - 6. A micro-hotplate device according to any of the claims 1-5, wherein said membrane consists of one or several insulator layers.
- 7. A micro-hotplate device according to claim 6, wherein at least one insulator is silicon nitride.
  - 8. A micro-hotplate device according to claim 6 or 7, wherein electrically conducting leads to the active microelectronic devices on the island have been placed between different insulator layers.
- 9. A micro-hotplate device according to any of the claims 1-8, wherein the 30 semiconducting material in the island is silicon.
  - 10. A micro-hotplate device according to any of the claims 1-8, wherein the semiconducting material in the island is silicon carbide.
    - 11. A micro-hotplate device according to any of the claims 1-10, wherein the support

## SUBSTITUTE SHEET (RULE 26)

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substrate and the island are made of the same material.

- 12. A method for the fabrication of a micro-hotplate device according to claim1, characterized in the use of a combination of masking steps and etching steps to define the geometry of the device.
- 13. A method according to claim 12, characterized in the use of consecutive backside etching steps comprising:
  - a) depositing the supporting membrane over the silicon substrate;
  - b) one etching step is used to define the thickness of the island by etching away the region surrounding the island to a certain wanted depth, equal to the wanted thickness of the island;
  - c) another etching step is used to etch the island and surrounding region until the island is isolated from the support substrate.
- 14. A method according to claim 12, characterized in the use of a silicon-on-insulator wafer as substrate whereby the buried insulator layer in said silicon-on-insulator wafer is used as an etch stop to define the thickness of the island of the device, resulting in a silicon island with an insulator layer on backside.
  - 15. A method according to claim 14, characterized in the use of the following steps:
    - etching away from the front side of the device the region surrounding the island down to the buried insulator layer,
    - b) etching away from the back side of the device the silicon in the region below the island and the region surrounding the island until the buried insulator layer on the island is exposed and the island is attached to the support by the insulator layer.
  - 16. A method according to claim 14, characterized by the following steps:
    - a) oxidizing the silicon layer on the front side of the device down to the buried insulator layer, except for the region where the island should be;
    - b) etching away from the front side of the device the oxide in the region surrounding the island until the underlying silicon substrate is exposed;
    - c etching away from the back side of the device the silicon in the region below the island until the buried insulator layer on the island is exposed and the island is attached to the support by the remaining part of the insulator layer.
- 17. A method according to any of the claims 12-16, wherin at least one of said etching steps is an anisotropic potassium hydroxide etching step.
  - 18. A method according to any of the claims 12-16, wherein at least one of said etching

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steps is an anisotropic tetramethyl ammonium hydroxide etching step.

- 19. A method according to any of the claims 12-16, at least one of said etching steps is a deep reactive ion etching step.
- 20. A micro-hotplate device according to any of the claims 1-12, wherein one or several of the chemical sensors utilize the field-effect detection mechanism.
- 21. A micro-hotplate device according to claim 20, wherein one or several field-effect chemical sensors are combined with one or several chemical sensors that utilize a detection mechanism different from the field effect.
- 22. A micro-hotplate device according to any of the claims 1-12 or 21, wherein one or 10 several of the chemical sensors are operated as gas sensors.
  - 23. A micro-hotplate device according to claims 21 and 22, wherein one or several fieldeffect gas sensors are combined with one or several gas sensors that utilize resistance changes as detection mechanism.
  - 24. A micro-hotplate device according to claim 23, wherein at least one of the gas sensors that utilize resistance changes as detection mechanism is made of a semiconducting metal oxide.
    - 25. A micro-hotplate device according to claim 23, wherein at least one of the gas sensors that utilize resistance changes as detection mechanism is made of a polymer.
    - 26. A micro-hotplate device according to any of the claims 1-12 or 20-25, wherein the support substrate contains an array of several islands.

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# **PCT**

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INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Article 36 and Rule 70)

Applicant's or agent's file reference P9918PC	FOR FURTHER ACTION	See Notific Preliminary	ation of Transmittal of International Examination Report (Form PCT/IPEA/416)
International application No.	International filing date (day/m	onth/year)	Priority date (day/month/year)
PCT/SE00/01134	31.05.2000		04.06.1999
International Patent Classification (IPC) of	r national classification and IPC	7	
G 01 N 27/414, G 01 N			
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Applicant	7D -+ -1		
Appliedsensor Sweden	AB et al		
This international preliminary exa Authority and is transmitted to the  This REPORT consists of a total  This report is also accompany to the second of	of 3 sheets, including to ANNEXES, i.e., sheets	36. ding this cover of the descript	
(see Rule 70.16 and Sectio	n 607 of the Administrative Instr	uctions under	the PCT).
These annexes consist of a total	of 2 sheets.		·
This report contains indications r	elating to the following items:		
I Basis of the report			
II Priority			
III Non-establishment of	of opinion with regard to novelty	, inventive step	and industrial applicability
IV Lack of unity of inv	ention		
V		to novelty, inv	entive step or industrial applicability;
VI Certain documents of			
	e international application		•
	s on the international application		
Date of submission of the demand	Date	of completion	of this report
20.12.2000	20	.09.2001	
Name and mailing address of the IPEA/S	SE Auti	norized officer	
Patent- och registreringsverket Box 5055	Telex 17978		
S-102 42 STOCKHOLM	•	rtil Dah	
Ecosimila No. 00-667 72 99	l Tele	nnone No. O.R.	-782 25 00



## INTERNATIONAL PRELIMINARY EXAMINATION REPORT

International application No.	
PCT/SE00/01134	

I.	Basi	Basis of the report	
1.	With r	ith regard to the elements of the international application:*	
		the international application as originally filed	
	$\boxtimes$	the description:	
		pages <u>1-6</u>	, as originally filed
		pages	, filed with the demand
	<b>₹</b>	pages, filed with	i die leder of
	$\bowtie$	the claims:	والمالية المناسبة المالية والمالية والمالية والمالية والمالية والمالية والمالية والمالية والمالية والمالية والم
		pages 8	, as originally filed
		pages, as amende	ed (together with any statement) under article 19
		pages 7,9 , filed with	
	$\triangleright$		<u> </u>
	$\triangle$	the drawings:	, as originally filed
		pages 1-2	, filed with the demand
		pages, filed with	1 the letter of
		the sequence listing part of the description:	
	لـــا	pages	, as originally filed
		pages	, med with the demand
		pages, filed with	
	the in These	With regard to the language, all the elements marked above were available or furning international application was filed, unless otherwise indicated under this item. These elements were available or furnished to this Authority in the following lang the language of a translation furnished for the purposes of international seather language of publication of the international application (under Rule 48. the language of the translation furnished for the purposes of international por 55.3).  With regard to any nucleotide and/or amino acid sequence disclosed in the international process of the sequence listing:  contained in the international application in written form.	which is:  arch (under Rule 23.1(b)).  3(b)).  breliminary examination (under Rules 55.2 and/  rnational application, the international
		filed together with the international application in computer readable form.	•
1	닏	furnished subsequently to this Authority in written form.	
		furnished subsequently to this Authority in computer readable form.  The statement that the subsequently furnished written sequence listing doe international application as filed has been furnished.  The statement that the information recorded in computer readable form is in been furnished.	
	4.	The amendments have resulted in the cancellation of:	
		the description, pages	
		the claims, Nos.	
		the drawings, sheet/fig	
,	5.	This report has been established as if (some of) the amendments had not beyond the disclosure as filed, as indicated in the Supplemental Box (Rule	een made, since they have been considered to go :70.2 (c)).**
	in th	Replacement sheets which have been furnished to the receiving Office in responsin this report as "originally filed" and are annexed to this report since they do rand 70.17).	se to an invitation under Article 14 are referred to not contain amendments (Rules 70.16
		and 70.17).  Any replacement sheet containing such amendments must be referred to under it	tem I and annexed to this report.



Claims

International application No.
PCT/SE00/01134

NO

V.	Reasoned statement under Article citations and explanations suppor	e 35(2) with r	egard to novelty, inventive step or industrial applicability; tement	y; 	
1.	Statement				
	Novelty (N)	Claims Claims	1-27	YES NO	
	Inventive step (IS)	Claims Claims	1-27	YES NO	
	Industrial applicability (IA)	Claims	1-27	_ YES	

#### 2. Citations and explanations (Rule 70.7)

The present application relates to a micro-hotplate device with integrated chemical sensors and a method for making it. The characterising feature of amended claim 1 is that at least one of the sensors is a gas-sensitive field-effect sensor.

The cited documents WO 94/10822 A1 (D1) and WO 94/10821 (D2) disclose micro-hotplate devices including means for measuring temperature and electric properties of materials during heating.

None of the documents, however, disclose a micro-hotplate device including a gas-sensitive field-effect sensor.

The device and method according to amended claims 1-27 are therefore novel. They are also considered to satisfy the criteria of inventive step, since it becomes possible to use chemical sensors of the gas-sensitive field-effect type in a micro-hotplate device, and industrial applicability.

#### INTERNATIONAL SEARCH REPORT

International application No.

PCT/SE 00/01134

## A. CLASSIFICATION OF SUBJECT MATTER IPC7: G01N 27/414, G01N 27/18 According to International Patent Classification (IPC) or to both national classification and IPC **B. FIELDS SEARCHED** Minimum documentation searched (classification system followed by classification symbols) IPC7: GO1N Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched SE,DK,FI,NO classes as above Electronic data base consulted during the international search (name of data base and, where practicable, search terms used) C. DOCUMENT'S CONSIDERED TO BE RELEVANT Category\* Citation of document, with indication, where appropriate, of the relevant passages Relevant to claim No. X WO 9410822 A1 (THE UNITED STATES OF AMERICA AS 1-26 REPRESENTED BY THE UNITED STATES DEPARTMENT OF COMMERCE), 11 May 1994 (11.05.94), page 8, line 2 - line 3; page 3, line 18 - page 4, line 20, figure 5 X WO 9410821 A1 (UNITED STATES OF AMERICA, AS 1-26 REPRESENTED BY THE UNITED STATES DEPARTMENT OF COMMERCE), 11 May 1994 (11.05.94), abstract Further documents are listed in the continuation of Box C. See patent family annex. Special categories of cited documents: later document published after the international filing date or priority date and not in conflict with the application but cited to understand the principle or theory underlying the invention "A" document defining the general state of the art which is not considered to be of particular relevance "E" erlier document but published on or after the international filing date "X" document of particular relevance: the claimed invention cannot be considered novel or cannot be considered to involve an inventive step when the document is taken alone document which may throw doubts on priority claim(s) or which is cited to establish the publication date of another citation or other special reason (as specified) document of particular relevance: the claimed invention cannot be considered to involve an inventive step when the document is combined with one or more other such documents, such combination document referring to an oral disclosure, use, exhibition or other heing obvious to a person skilled in the art document published prior to the international filing date but later than the priority date claimed "&" document member of the same patent family Date of the actual completion of the international search Date of mailing of the international search report 0 9 -10- 2000 <u> 28 Sept 2000</u> Name and mailing address of the ISA/ Authorized officer **Swedish Patent Office** Box 5055, S-102 42 STOCKHOLM Moa Grönkvist/ELY Facsimile No. +46 8 666 02 86 Telephone No. +46 8 782 25 00

## INTERNATIONAL SEARCH REPORT

Information on patent family members

International application No.

01/08/00

PCT/SE 00/01134

Patent document cited in search report			Publication date		atent family member(s)	Publication date
WO	9410822	A1	11/05/94	US	5464966 A	07/11/95
WO	9410821	A1	11/05/94	AU US	5450194 A 5356756 A	24/05/94 18/10/94

Form PCT/ISA/210 (patent family annex) (July 1992)